

IN THE CLAIMS

This listing of claims will replace all prior versions, and listings, of claims in the application:

Listing of Claims:

Claims 1-6 (Canceled)

7. (Currently Amended) A mask having a mask pattern which comprises at least one diffraction structure for deflecting incident radiation in a plane comprising the direction of periodicity of the diffraction structure and the propagation direction of the incident radiation, wherein the at least one diffraction structure includes a first structure having strips of a first pitch and a second structure having strips of a second pitch which is different from the first pitch.

8. (Previously Presented) The mask of claim 7, wherein the diffraction structure is an amplitude structure.

9. (Previously Presented) The mask of claim 7, wherein the diffraction structure is a phase structure.

10. (Previously Presented) The mask of claim 9, wherein the phase structure has a duty cycle of 50% and a phase depth of  $180^\circ$ .

11. (Previously Presented) The mask of claim 7, wherein the diffraction structure is designed to deflect incident exposure radiation at an angle of substantially  $20^\circ$  to the normal to the grating surface.

12. (Currently Amended) The mask of claim 7, wherein the mask pattern comprises, next to a diffraction structure, mask features corresponding to substrate features to be configured in a substrate upper surface layer layer.

13. (Previously Presented) The mask of claim 7, layer the diffraction structure is a linear diffraction grating.

14. (Previously Presented) The mask of claim 7, layer the diffraction structure is a two-dimensional diffraction grating.

15. (Previously Presented) The mask of claim 7, layer the diffraction structure comprises a number of linear diffraction gratings, which each form a segment of a common circular area.

Claim 16 (Canceled)

17. (Currently Amended) A mask having a mask pattern which comprises at least one diffraction structure for deflecting incident radiation in a plane comprising the direction of periodicity of the diffraction structure and the propagation direction of the incident radiation, the diffraction structure corresponding to a substrate feature to be configured in a substrate side surface layer, wherein the at least one diffraction structure includes a first structure having strips of a first pitch and a second structure having strips of a second pitch which is different from the first pitch.